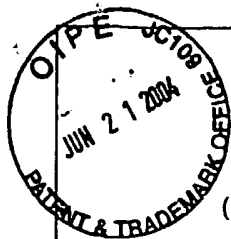


06/21/2004


**INFORMATION DISCLOSURE
STATEMENT BY APPLICANT**

 Form PTO-1449 (Modified)
(Use several sheets if necessary)

COMPLETE IF KNOWN

Application Number	10/681,553
Confirmation Number	7774
Filing Date	October 7, 2003
First Named Inventor	Eric J. BERGMAN
Group Art Unit	1746
Examiner Name	
Attorney Docket No.	54008.8012.US04 (P96-0015US5)

Sheet

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of

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U.S. PATENT DOCUMENTS

Examiner Initials*	Cite No.	U.S. Patent or Application		Name of Patentee or Inventor of Cited Document	Date of Publication or Filing Date of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		NUMBER	Kind Code (if known)			
MK	EZ	6,551,409		DeGendt	04/22/03	
MK	FA	2002/0011257		DeGendt	01/31/02	

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OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume issue number(s), publisher, city and/or country where published.	T
MK	FB	Golland, D.E., et al., "The Clean Module: Advanced Technology for Processing Silicon Wafers." <i>Semiconductor Int'l.</i> , pp. 154-157 (Sep. 1987).	

EXAMINER

DATE CONSIDERED

08/18/04


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[54008.8012.US04/LA041610.077]

10/07/2003

EM No. EV 254990096US				COMPLETE IF KNOWN	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT Form PTO-1449 (Modified) (Use several sheets if necessary)				Application Number	Not yet assigned
				Confirmation Number	
				Filing Date	October 7, 2003
				First Named Inventor	Eric J. BERGMAN
				Group Art Unit	
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Sheet	1	of	5	Attorney Docket No.	54008.8012.US04

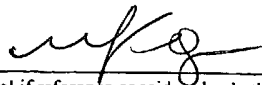
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		NUMBER	Kind Code (if known)			
MK	AA	5,055,138		Slinn	10/08/91	
	AB	5,120,370		Mori et al.	06/09/92	
	AC	5,647,386		Kaiser	07/15/97	
	AD	5,503,708		Koizumi et al.	04/02/96	
	AE	5,308,745		Schwartzkopf	05/03/94	
	AF	4,695,327		Grebinski	09/22/87	
	AG	5,632,847		Ohno et al.	05/27/97	
	AH	5,911,837		Matthews	06/15/99	
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	AJ	5,244,000		Stanford et al.	09/14/93	
	AK	5,896,875		Yoneda	04/27/99	
	AL	4,974,530		Lyon	12/04/90	
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	AP	5,520,744		Fujikawa et al.	05/28/96	
	AQ	5,415,191		Mashimo et al.	05/16/95	
	AR	5,658,615		Hasebe et al.	08/19/97	
	AS	5,858,107		Chao et al.	01/12/99	
	AT	5,971,368		Nelson et al.	10/26/99	
	AU	5,234,540		Grant et al.	08/10/93	
	AV	5,803,982		Kosofsky et al.	09/08/98	
	AW	5,944,907		Ohmi	08/31/99	
	AX	5,232,511		Bergman	08/03/93	
	AY	5,776,296		Matthews	07/07/98	
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	BA	6,267,125		Bergman et al.	07/31/01	
	BB	6,273,108		Bergman et al.	08/14/01	
	BC	6,146,469		Toshima	11/14/00	
	BD	4,917,123		McConnell et al.	04/17/90	
	BE	4,749,440		Blackwood et al.	06/07/88	
	BF	4,817,652		Liu	04/04/89	
	BG	5,571,367		Nakajima et al.	11/05/96	
	BH	5,063,609		Lorimer	11/05/91	
	BI	5,246,526		Yamaguchi et al.	09/21/93	
	BJ	5,372,651		Kodama	12/13/94	
	BK	3,898,141		Ermanis et al.	08/05/75	
MK	BL	4,050,954		Basi	09/27/77	

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				First Named Inventor	Eric J. BERGMAN
				Group Art Unit	
Examiner Name					
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		NUMBER	Kind Code (if known)			
MC	BM	4,261,791		Shwartzman	04/14/81	
	BN	4,264,374		Beyer et al.	04/28/81	
	BO	4,615,762		Jastrzebski	10/07/86	
	BP	4,899,767		McConnell	02/13/90	
	BQ	4,943,540		Ren et al.	07/24/90	
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	BS	5,181,985		Lampert et al.	01/26/93	
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	BX	5,158,100		Tanaka et al.	10/27/92	
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	CF	5,832,177		Shinagawa et al.	11/03/98	
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		Office	NUMBER	Kind Code (if known)				
MC	CI	JP	4-302,144		Hitachi, Ltd.	10/26/1992		
	CJ	EP	0 782 177 A2		Texas Instruments Incorporated	07/02/1997		
	CK	JP	H03-208900		Susumu Otsuka et al.	09/12/1991		
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	CO	JP	8-8222		Sony Corporation	01/12/1996		
	CP	JP	52-12063		Hiroshi Ikeda	04/04/1977		
MC	CQ	JP	H04-125927		Yutaka Watarai et al.	04/27/1992		

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		Office	Kind Code (if known)					
MK	CR	JP	05-013398	Hitachi Zosen Corp.	01/22/1993			
	CS	JP	H01-262627	Mikio Tsuji	10/19/1989			
	CT	JP	04-370931	Hitachi Zosen Corp.	12/24/1992			
	CU	JP	05-283389	NEC Corp.	10/29/1993			
	CV	JP	03-072626	Dainippon Screen Mfg. Co., Ltd.	03/27/1991			
	CW	JP	06-204130	Mitsubishi Electric Corp.	07/22/1994			
	CX	JP	04-302145	Hitachi Ltd.	10/26/1992			
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	DD	JP	02-164035	NEC Corp.	06/25/1990			
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	DG	JP	05-047741	Dainippon Screen Mfg. Co.	02/26/1993			
	DH	JP	04-326516	NEC Corp.	11/16/1992			
	DI	JP	62 118528	Matsushita Electronics Corp.	05/29/1987			
	DJ	JP	05-183151	Matsushita Elec. Ind. Co. Ltd.	07/23/1993			
	DK	EU	0 472 441	Seiko Epson Corp.	08/1991			
	DL	EU	0 548 596	Matsuoka Terumi	11/30/1992			
	DM	EU	0 587 889	Ohmi Tadahiro	05/13/1992			
MK	DN	JP	04 301245	Canon Inc.	10/23/1992			

OTHER PRIOR ART-NON PATENT LITERATURE DOCUMENTS			
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MK	DO	Abstract of JP 3041729 published 2/22/91.	
	DP	Heyns, M.M., et al. "New Wet Cleaning Strategies for Obtaining Highly Reliable Thin Oxides," MRP Symposium Proceedings on Materials Research Society, Spring Meeting, San Francisco, CA April 12-13, 1993, p. 35 (1993)	
	DQ	Adler, Marilyn Grace and Hall, George Richard, "The Kinetics and Mechanism of Hydroxide Ion Catalyzed Ozone Decomposition in Aqueous Solution" <i>J. Am. Chem. Soc.</i> , Volume 72, pp. 1884-86, 1950.	
MK	DR	Nelson, Steve, "Ozonated water for photoresist removal" <i>Solid State Technology</i> , pp. 107-112 (July 1999)	

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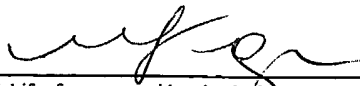
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MK	DS	Christenson, Kurt K., et al. "Deionized Water Helps Remove Wafer Stripping 'Resist'-ance," <i>www.precisioncleaningweb.com - Precision Cleaning Web - Archives</i> , pp. 10-20 (April 1998)	
MK	DT	Sehested, K., et al., "Decomposition of Ozone in Aqueous Acid Solutions (pH 0-4)," <i>J. Phys. Chem.</i> , pp. 1005-1009 (1992)	
MK	DU	Krusell, W.C. et al., "Cleaning Technology for High Volume Production of Silicon Wafers," <i>ECS Proc. of the First Int'l. Symposium on Cleaning Technology I Semiconductor Device Mfg.</i> , pp. 23-32 (October 1989)	
	DV	Vig, John R., "UV/Ozone Cleaning of Surfaces," U.S. Army Elec. Tech. and Devices Lab., pp. 1-26	
MK	DW	Vig, John R., "UV/Ozone Cleaning of Surfaces: A Review," <i>Surface Contamination: Genesis, Detection, and Control</i> , pp. 235-253(1979)	
	DX	Tong, Jeremy, et al., "Aqueous Ozone Cleaning of Silicon Wafers," <i>ECS Extended Abstracts, Phoenix, AZ</i> , Abstract No. 506, pp. 753 (October 13-17, 1991)	
	DY	Zafonte, Leo, et al., "UV/Ozone Cleaning For Organics Removal on Silicon Wafers," <i>SPIE Optical Microlithography III: Technology for the Next Decade</i> , Vol. 470, pp. 164-175 (1984)	
	DZ	Baumgärtner, H., et al., "Ozone Cleaning of the Si-SiO ₂ System," <i>Appl. Phys. A</i> , Vol. 43, pp. 223-226 (1987)	
	EA	Isagawa, Tatsuhiko, et al., "Ultra Clean Surface Preparation Using Ozonized Ultrapure Water," <i>Extended Abstracts of the 1982 Int'l. Conf. on Solid State Devices and Materials</i> , pp. 193-195 (1992)	
	EB	Shimada, H., et al., "Residual-Surfactant-Free Photoresist Development Process," <i>J. Electrochem. Soc.</i> , 139(6):1721-1730 (June 1992)	
	EC	Tong, Jeremy K. et al., "Aqueous Ozone Cleaning of Silicon Wafers," <i>Proc. of 2nd Int'l. Symposium on Cleaning Tech. In Semiconductor Device Mfg.</i> , pp. 18-25 (October 1992)	
	ED	Tong, Jeremy K., et al., "Aqueous Ozone Cleaning of Silicon Wafers," <i>Res. Soc. Symp.</i> , pp. 18-25 (1993)	
	EE	Ohmi, T., et al., "Native Oxide Growth and Organic Impurity Removal on Si Surface with Ozone-Injected Ultrapure Water," <i>J. Electrochem. Soc.</i> , 140(3):804-810 (March 1993)	
	EF	Vig, John R., et al., "UV/Ozone Cleaning of Surfaces," <i>IEEE Transactions on Parts, Hybrids, and Packaging</i> , Vol. PHP-12(4):365-370 (December 1976)	
	EG	Vig, John R., "UV/ozone cleaning of surfaces," <i>U.S. Army Electronics Technology and Devices Laboratory, ERADCOM, Ft. Monmouth, NJ, 07703-5302</i> , pp. 1027-1034 (September/October 1984)	
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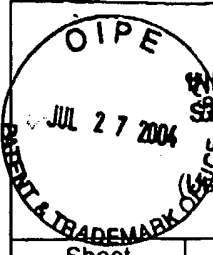
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MK	EL	Kern, Werner, "The Evolution of Silicon Wafer Cleaning Technology," <i>J. Electrochem. Soc.</i> , 137(6):1887-1892 (June 1990)		
	EM	Kasi, S.R., et al., "Surface Hydrocarbon Removal from Si by UV/Ozone," <i>ECS Extended Abstracts</i>, No. 458, pp. 691-692 (199)		
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	EQ	Goulding, M.R., "The selective epitaxial growth of silicon," <i>Materials Science and Engineering</i> , Vol. B17, pp. 47-67 (1993)		
	ER	Ganesan, Gans S., et al., "Characterizing Organic Contamination in IC Package Assembly," <i>The Int'l. Soc. for Hybrid Microelectronics</i> , Vol. 17, #2, Second Quarter, pp. 152-160 (1994)		
	ES	Egitto, F.D., et al., "Removal of Poly(Dimethylsiloxane) Contamination From Silicon Surfaces With UV/Ozone Treatment," <i>Mat. Res. Soc. Symp. Proc.</i> , Vol. 385, pp. 245-250 (1995)		
	ET	Amick, J.A., "Cleanliness and the Cleaning of Silicon Wafers," <i>Solid State Technology</i> , pp. 47-52 (November 1976)		
	EU	Bolon, D.A., et al., "Ultraviolet Depolymerization of Photoresist Polymers," <i>Polymer Engineering and Science</i> , 12(2):108-111 (March 1972)		
	EV	Krusell, W.C., et al., "The Characterization of Silicon Substrate Cleaning Treatments by use of SIMS and MOS Electrical Testing," <i>ECS Extended Abstracts</i> , No. 229, p. 331-332 (1986)		
	EW	Anantharaman, Ven, Ph.D., et al., "ORGANICS: Detection and Characterization of Organics in Semiconductor DI Water Processes," <i>Ultracure Water</i> , pp. 30-36 (April 1994)		
	EX	"Ozone Concentration Measurement In A Process Gas," <i>Proposed IOA Pan American Group Guideline</i> , pp. 1-21 (December 1993)		
MK	EY	"Ozone for Semiconductor Applications," <i>Sorbios</i> , pp. 1-6 (October 1991)		

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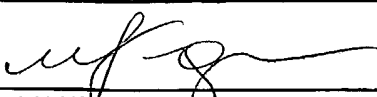
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MK	FC	6,589,359 B2		Kamikawa et al.	07/10/01	

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